

ABSTRACT OF THE DISCLOSURE

HYDROLYTICALLY STABLE ORGANIC POLYMER MATERIAL FOR ORGANIC POLYMER ANTI-REFLECTIVE (ARC) LAYER

A method for forming an anti-reflective coating (ARC) layer within a fabrication and a fabrication having the anti-reflective coating (ARC) layer formed therein. To practice the method, there is first provided a substrate. There is then formed over the substrate a reflective layer. There is then formed upon the reflective layer an organic polymer anti-reflective coating (ARC) layer, where the organic polymer anti-reflective coating (ARC) layer is formed from an organic polymer anti-reflective coating (ARC) material which is not susceptible to a hydrolysis reaction. There may then be formed upon the organic polymer anti-reflective coating (ARC) layer a photoresist layer which is photoexposed and developed to form a patterned photoresist layer which may be employed as an etch mask for forming a patterned reflective layer from the reflective layer. The patterned reflective layer so formed is formed with uniform and reproducible linewidth dimension.

(FIGURE 1 IS SUGGESTED FOR PUBLICATION)